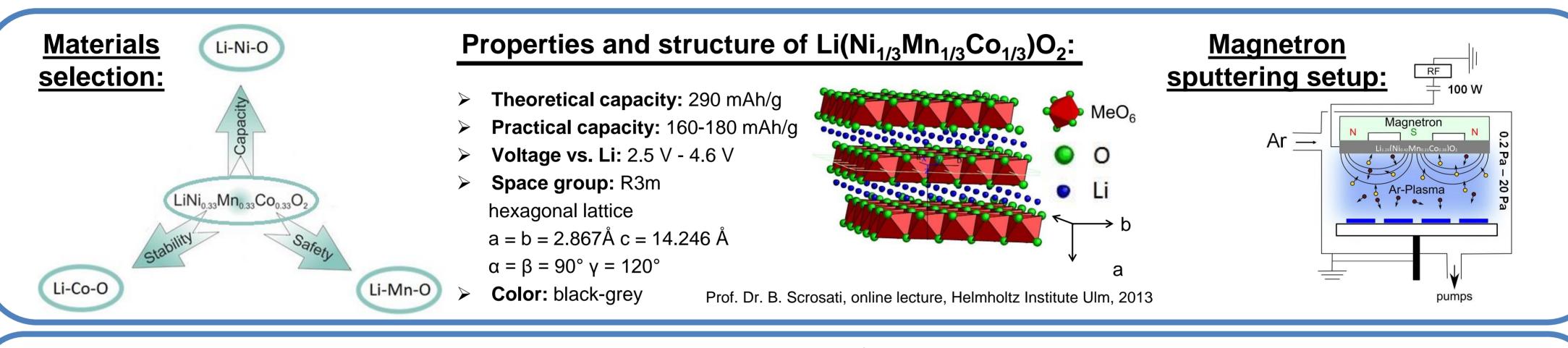
AP 2.1

Structuring and processing of electrodes

Constitution and microstructure of Li-Ni-Mn-Co-O thin film cathodes

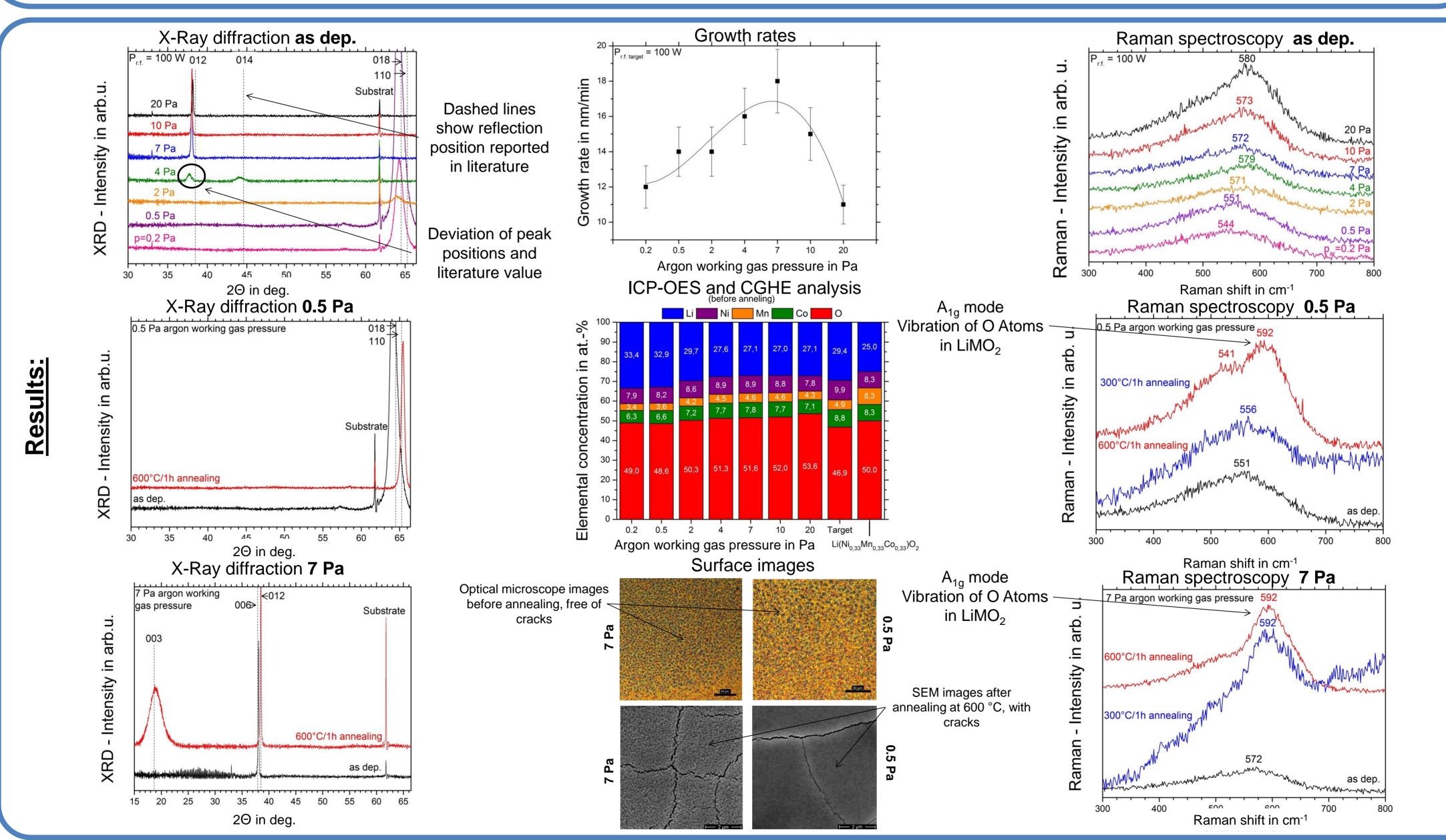
1.5 µm thick Li-Ni-Mn-Co-O cathodes have been deposited by r.f. magnetron sputtering from Li_{1.25}(Ni_{0.42}Mn_{0.21}Co_{0.37})O₂ target. The elemental composition varies with argon working gas pressure (0.2 Pa to 20 Pa) and was determined by inductively coupled plasma-optical emission spectroscopy (ICP-OES) in combination with carrier gas hot extraction. The microstructure of the films was characterized by X-ray diffraction (XRD) and by micro-Raman spectroscopy at room temperature. The as-deposited films are nanocrystalline and show their highest grade of crystallinity in the range between 0.2 Pa to 0.5 Pa and at 7 Pa. Correlations between process parameter, constitution and microstructure are discussed in detail.



Deposition parameters: Argon working gas pressure: 0.2 Pa to 20 Pa / target power: 100 W film thickness: ~1.5 μm

Annealing parameters: 300 °C / 600 °C, 1 hour, 10 Pa Ar/O₂ (80:20)-atmosphere

Li(Ni-Mn-Co) O_2 {1.5 µm} Si (001) {substrate}



Conclusions and Outlook:

- Li-Ni-Mn-Co-O thin films were synthesised with different microstructures and elemental compositions.
 - The X-Ray reflections deviate from positions reported in literature.

 | Intercomposition | Probably squared by residual stresses or different elemental of the probably squared by residual stresses or different elemental of the probably squared by residual stresses.

The difference is probably caused by residual stresses or different elemental composition.
At 0.5 Pa and 7 Pa the as deposited films show the highest grade of crystallinity.

Next steps will be annealing in different atmospheres, investigations of the electrochemical behavior, surface modifications with laser and plasma technology, development of an artificial SEI.

rent microstructures and elemental compositions. The authors gratefully acknowledge the financial

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